This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS

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-1-(Currently Amended)

A process for producing heteroepitaxial growth of a single crystal diamond film which comprises:

- (a) forming an atomically flat stepped surface on a single crystal metal oxide substrate which has a crystal structure for depositing a film of epitaxial iridium to produce a (001) film on the surface;
- (b) depositing the film of the epitaxial iridium metal on the <u>metal</u> oxide so that the (001) surface results;
 - (CVD) of diamond nuclei onto the iridium film on the substrate, which is mounted on a holder for the substrate which holder has a negative bias and which holder comprises an insulating shield and a cap in the plasma, wherein the diamond nuclei emerge from a plasma

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produced from a mixture comprising methane and hydrogen gases with dc-biased ion bombardment onto the iridium film from the gases; and

(d) growing the diamond film on the diamond nuclei condensate and iridium film using CVD and the mixture of the methane and the hydrogen, without the dc-biased ion bombardment to form the single crystal diamond.

-2-(Original)

The process of Claim 1 wherein in step a) the metal oxide substrate is selected from the group consisting of sapphire, strontium titanate, lanthanum aluminate and magnesium oxide.

-3-(Original)

The process of Claim 1 wherein in step a) the atomically flat surface is provided by chemical, mechanical or thermal means.

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-4-(Original)

The process of Claim 1 wherein the d.c. bias is between -100 and -300 volts relative to a bias ring located within the plasma above the substrate.

-5-(Original)

The process of any one of Claims 1, 2, 3 or 4 wherein the microwave frequency is between 900 MHz and 2.5 GHz, the methane to hydrogen ratio is between 0.002 and 0.04, and the temperature is between about 650 and 850°C.

-6-(Original)

The process of Claim 1 wherein the substrate is electrically isolated from a support during the CVD.

-7-(Original)

The process of any one of Claims 1, 2, 3 or 4 wherein the gases are essentially free of nitrogen.

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-8-(Currently Amended)

A process for producing a composite composition which comprises:

- (a) forming atomically flat stepped surface on a single crystal metal oxide which has a crystal structure for depositing a film of epitaxial iridium to produce a (001) film on the surface;
- (b) depositing the film of epitaxial iridium metal on the <u>metal oxide</u> surface so that the (001) surface results; and
- (c) depositing <u>diamond</u> nuclei on the iridium film by chemical vapor deposition (CVD) from a plasma produced from a mixture comprising methane and hydrogen gases with dc-biased ion bombardment onto the iridium film on the substrate, which is mounted on a holder for the substrate which holder has a negative bias and which holder comprises an insulating shield and a cap in the plasma, from the gases to produce the composite composition.

-9-(Original)

The process of Claim 8 wherein the substrate is sapphire.

-10-(Original)

The process of Claim 8 wherein the dc bias is between -100 and -300 volts relative to a bias ring located in the plasma above the surface.

-11-(Original)

The process of any one of Claims 8, 9 and 10 wherein the microwave frequency is between 900 MHz and 2.5 GHz, the methane to hydrogen rate is between 0.002 and 0.04 and the temperature is between 650 and 850°C.

-12-(Original)

The process of Claim 1 wherein the substrate is electrically isolated during the CVD.

-13-(Currently Amended)

The process of any one of Claims 8, $\frac{9}{7}$ 10 or 12 wherein the gases are essentially free of nitrogen.

Claims 14-17 (Cancelled)